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APPLICATION NO.	NO. FILING DATE		FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/672,895	5 09/26/2003		Mira Ben-Tzur	10002.000810 (PM02006-2)		
31894	7590	05/11/2004		EXAMINER		
OKAMOT P.O. BOX 6		NEDICTO, LLP	NGUYEN, TUAN H			
SAN JOSE, CA 95164				ART UNIT	PAPER NUMBER	
•				2813		
				DATE MAILED: 05/11/2004	DATE MAILED: 05/11/2004	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Anglicant(a)				
		Application No.	Applicant(s)				
	000 4-4	10/672,895	BEN-TZUR ET AL.	BEN-TZUR ET AL.			
	Office Action Summary	Examiner	Art Unit				
		Tuan H. Nguyen	2813	and a			
Period fo	The MAILING DATE of this communication app or Reply	ears on the cover sheet with th	e correspondence addr	ess			
THE - Exte after - If the - If NO - Failt Any	ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. nsions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. e period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply by within the statutory minimum of thirty (30) will apply and will expire SIX (6) MONTHS to cause the application to become ABANDO	e timely filed  days will be considered timely.  rom the mailing date of this comr  DNED (35 U.S.C. § 133).	nunication.			
Status							
1)⊠	Responsive to communication(s) filed on 26 Se	eptember 2003.					
•		action is non-final.					
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Disposit	ion of Claims						
5)	Claim(s) 13,15-19 and 21-26 is/are pending in 4a) Of the above claim(s) is/are withdraw Claim(s) is/are allowed.  Claim(s) 13,15-19, 21-26 is/are rejected.  Claim(s) is/are objected to.  Claim(s) are subject to restriction and/or ion Papers  The specification is objected to by the Examine The drawing(s) filed on is/are: a) according a control of the drawing of the specification to the original or specification and original origina	vn from consideration.  r election requirement.  r.  epted or b) □ objected to by the	•				
11)[	Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Ex	ion is required if the drawing(s) is	objected to. See 37 CFR	` '			
Priority (	under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).  a) All b) Some * c) None of:  1. Certified copies of the priority documents have been received.  2. Certified copies of the priority documents have been received in Application No  3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).  * See the attached detailed Office action for a list of the certified copies not received.							
2) Notice 3) Information	te of References Cited (PTO-892) se of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) er No(s)/Mail Date 12/29/03.	4) Interview Summ Paper No(s)/Ma 5) Notice of Inform 6) Other:		52)			

## **DETAILED ACTION**

## Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in-
- (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effect under this subsection of a national application published under section 122(b) only if the international application designating the United States was published under Article 21(2)(a) of such treaty in the English language; or
- (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that a patent shall not be deemed filed in the United States for the purposes of this subsection based on the filing of an international application filed under the treaty defined in section 351(a).

Claims 13,16,18, 22, 23, 24, 25 are rejected under 35 U.S.C. 102(e) as being anticipated by Allman et al..

See Allman et al.. figs. 1-2 and related text on col. 2-3 which discloses the claimed integrated circuit structure including a last metal level 28 comprising a plurality of metal lines over a first dielectric layer 26; a passivation level comprising a low-k dielectric layer 30, 34 substantially filling space extending between metal lines 28 (fig. 2, col. 2, lines 25-63). The low-k dielectric 30, 34 filling more than about 50% of a distance between a sidewall of a metal line and a sidewall of an adjacent metal line in the plurality of metal lines 28.

With respect to claims 16, 22, 24, it is well-known that low-k dielectric material having dielectric constant of less than 3.9.

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With respect to claim 25, fig. 2 shows low-k dielectric layer 30, 34 is directly on the first dielectric 26.

Claims 13, 15-19, 21-26 are rejected under 35 U.S.C. 102(e) as being anticipated by Bohr.

See Bohr, figs. 2a-2i and related text on col. 3-6 which discloses the claimed structure in an integrated circuit including a last metal level 208; and a passivation level comprising a low-k dielectric 212 substantially fills a space between metal lines 208 in the last metal level for reducing the capacitive coupling between the conductors which in turns, reducing propagration delay of the signal (figs. 2a-2c and col. 3, lines 29 to col. 4, line 67).

With respect to claims 15, 21, 26, figs. 2e-2f show the passivation level further comprises a layer of dielectric 216 over the low-k dielectric 212 and a topside material 218 over the layer of dielectric 216 (col. 5, second and third paragraph).

With respect to claims 16, 22, 24, see col. 4, fourth paragraph for the low-k having dielectric constant of less than or equal 4.

With respect to claims 17, 19, see col. 3, lines 45-47 which discloses the metal thickness of between 1-3 microns which is within the claimed range.

With respect to claim 25, see col. 3, lines 13-21 wherein outer most surface of substrate 200 including insulating layer.

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Lou, Chang et al., Cha et al., Wong et al., and Coffman disclose the use of low-k dielectric material between aluminum metal lines for reducing RC constant.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Tuan H. Nguyen whose telephone number is 703-308-2550. The examiner can normally be reached on 9AM-5:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr. can be reached on 703-308-4940. The fax phone numbers for the organization where this application or proceeding is assigned are 703-872-9318 for regular communications and 703-872-9319 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

Tuan H. Nguyen Primary Examiner Art Unit 2813

man # Nguyen

TN May 6, 2004